

Appl. No. 09/997,882
Reply to Office action of 12/05/2003

Amendments to the Claims:

This listing of claims will replace all prior versions, and listings, of claims in the application:

Listing of Claims:

1. (amended) A chemical-mechanical polishing process comprising the steps of:
chemically mechanically polishing a gap fill material stopping on a first film;
stripping the first film to expose a second film;
after exposing the second film, chemically mechanically polishing the gap fill material and the second film stopping on a third film.
2. (original)The method of claim 1, wherein said first and third film comprise the same material.
3. (original)The method of claim 1, wherein said first film and said third film comprise silicon nitride.
4. (original)The method of claim 3, wherein the second film comprises silicon dioxide.
5. (original)The method of claim 1, wherein the third film has a thickness in the range of 30-50 nm.
6. (original)The method of claim 1, wherein said gap fill material forms a shallow trench isolation structure.

Cancel claims 7-16.